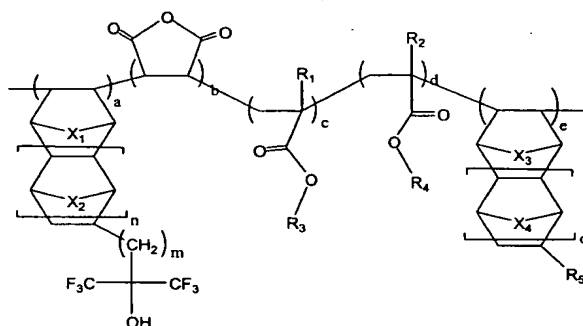


ABSTRACT OF THE DISCLOSURE

Photoresist polymers and photoresist compositions are disclosed. A photoresist polymer represented by Formula 1 and a photoresist composition containing the same have excellent etching resistance, thermal resistance and adhesive property, and high affinity to an developing solution, thereby improving LER (line edge roughness).

Formula 1



wherein

X₁, X₂, X₃, R₁, R₂, R₃, R₄, R₅, m, n, o, a, b, c, d and e are as defined in the description.